

L Number	Hits	Search Text	DB	Time stamp
1	2	jp-2000035665-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/09 08:57
-	2	((("20020068237") or ("20020068236")).PN.	US-PGPUB	2003/07/09 08:57
-	1975440	resin resist photoresist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:06
-	16077	(photoacid acid) near generat\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:06
-	78586	photosensitizer sensitizer	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:05
-	1008314	solvent <i>Fast Search</i>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/03 13:46
-	1234	(resin resist photoresist) and ((photoacid acid) near generat\$3) and (photosensitizer sensitizer) and solvent	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/03 13:49
-	5890	benzopyran	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:06
-	25	((resin resist photoresist) and ((photoacid acid) near generat\$3) and (photosensitizer sensitizer) and solvent) and benzopyran	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 11:40
-	155	IMAI-G IMAI-GENICHI IMAI-GENJI	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 16:22
-	6	(IMAI-G IMAI-GENICHI IMAI-GENJI) and benzopyran	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:01
-	78586	photosensitizer sensitizer	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:06
-	5890	benzopyran <i>DO NOT REMOVE</i>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:06
-	61	(photosensitizer sensitizer) same benzopyran	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:08
-	16077	(photoacid acid) near generat\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 17:04
-	1975440	resin resist photoresist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:06
-	7	((photosensitizer sensitizer) same benzopyran) and ((photoacid acid) near generat\$3) and (resin resist photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:07
-	3	((photosensitizer sensitizer) same benzopyran) and ((photoacid acid) near generat\$3) and (resin resist photoresist) not ((IMAI-G IMAI-GENICHI IMAI-GENJI) and benzopyran)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:07

-	20	((photosensitizer sensitizer) same benzopyran) and (resin resist photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:08
-	13	((((photosensitizer sensitizer) same benzopyran) and (resin resist photoresist)) not (((IMAI-G IMAI-GENICHI IMAI-GENJI) and benzopyran) (((photosensitizer sensitizer) same benzopyran) and ((photoacid acid) near generat\$3) and (resin resist photoresist)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:10
-	0	jp-8334897-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:10
-	2	jp-08334897-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:26
-	2	jp-11212252-\$.did. or jp-2000275823 or jp-2000056450	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:27
-	6	(jp-11212252-\$.did. or jp-2000275823 or jp-2000056450) jp-09138502-\$.did. jp-2000035665-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:27
-	2	jp-2000035665-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:49
-	2	titanocene same (\$5acid near generator)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 13:47
-	1	(titanocene adj compound) same (\$5acid near generator)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 13:47
-	0	((titanocene adj compound) same (\$5acid near generator)) not (titanocene same (\$5acid near generator))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 13:48
-	51	(radical adj generator) same ((acid photoacid) near generator)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:24
-	900	(resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 17:03
-	509	((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:26
-	3797882	photocurable curable cur\$5 negative crosslinkable crosslinked crosslink (cross adj link\$4) cross-link\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:27
-	509	((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and (photocurable curable cur\$5 negative crosslinkable crosslinked crosslink (cross adj link\$4) cross-link\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:28
-	4167371	dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:30

-	4553605	coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:31
-	1655136	irradiate irradiating expose exposure exposing exposed irradiated irradiation	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:31
-	1640490	develop development developing developed]	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:32
-	360309	(visible adj light) "VIS"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:32
-	57817	(dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed]) and ((visible adj light) "VIS")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:33
-	208	((((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed]) and ((visible adj light) "VIS"))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:37
-	50	((((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed]) and ((visible adj light) "VIS")) and (peel peeling peelable peeled (peel\$4-apart) (peel\$4 near apart))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:41
-	27	((((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed]) and ((visible adj light) "VIS")) and (peel peeling peelable peeled (peel\$4-apart) (peel\$4 near apart))	USPAT; EPO; JPO; DERWENT	2003/07/07 15:48
-	2	("6033826").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 15:48
-	1	((("6033826").PN.) and (generator) and (\$\$sensitizer)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 16:31

-	32	pyrene same (benzopyran)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 15:54
-	18	(((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed) and ((visible adj light) "VIS"))) and (peel peeling peelable peeled (peel\$4-apart) (peel\$4 near apart))) and ((visible VIS) near light)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 17:03
-	0	(((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed) and ((visible adj light) "VIS"))) and (peel peeling peelable peeled (peel\$4-apart) (peel\$4 near apart))) and ((visible VIS) near light)) and benzopyran	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 17:02
-	0	(((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation) and (develop development developing developed) and ((visible adj light) "VIS"))) and (peel peeling peelable peeled (peel\$4-apart) (peel\$4 near apart))) and benzopyran	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 17:02
-	2248	((visible adj light) "VIS") and benzopyran	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 17:02
-	395	((visible adj light) "VIS") and benzopyran) and ((visible VIS) near light)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 17:03
-	293	(resin resist photoresist binder) and (((visible adj light) "VIS") and benzopyran) and ((visible VIS) near light))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 17:03
-	21	((photoacid acid) near generat\$3) and ((resin resist photoresist binder) and (((visible adj light) "VIS") and benzopyran) and ((visible VIS) near light)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 17:45
-	1	ls-148	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 18:04
-	2	JP-11258798-\$.DID.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 18:04

-	2	benzopyran adj condensed adj ring	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 11:34
-	7521	condensed adj ring	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 11:53
-	72	proliferating adj agent	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 13:48
-	2661	sodium adj lamp	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 12:09
-	120	(sodium adj lamp) same (nm wavlength)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 12:10
-	72	proliferating adj agent	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 14:31
-	2	jp-09138502-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 13:50
-	2	("6140025").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 14:06
-	12	(proliferating adj agent) and (resin resist photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 14:09
-	0	(proliferating adj agent) same ((fluidity adj adjuster) (adhesion adj improver) (cissing adj inhibitor) (polymerization adj inhibitor) pigment plasticizer)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 14:35
-	134	(organic adj acid adj ester) same ((fluidity adj adjuster) (adhesion adj improver) (cissing adj inhibitor) (polymerization adj inhibitor) pigment plasticizer)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 14:58
-	83	((organic adj acid adj ester) same ((fluidity adj adjuster) (adhesion adj improver) (cissing adj inhibitor) (polymerization adj inhibitor) pigment plasticizer)) and (resist photoresist resin)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 14:58
-	79	((organic adj acid adj ester) same ((fluidity adj adjuster) (adhesion adj improver) (cissing adj inhibitor) (polymerization adj inhibitor) pigment plasticizer)) and (resist photoresist resin)	USPAT; EPO; JPO; DERWENT	2003/07/08 14:46
-	2648	(organic adj acid adj ester)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 14:58
-	1070	((organic adj acid adj ester)) and (resist photoresist resin)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 14:59
-	834	((organic adj acid adj ester)) and (resist photoresist resin)	USPAT	2003/07/08 15:13
-	0	430.270.1.ccls.	USPAT	2003/07/08 15:00
-	2718	430/270.1.ccls.	USPAT	2003/07/08 15:09
-	5	430/270.1.ccls. and (((organic adj acid adj ester)) and (resist photoresist resin))	USPAT	2003/07/08 15:01
-	6	430/270.1.ccls. and ((organic adj acid adj ester))	USPAT	2003/07/08 15:08

-	1	(430/270.1.ccls. and ((organic adj acid adj ester))) not (430/270.1.ccls. and (((organic adj acid adj ester)) and (resist photoresist resin)))	USPAT	2003/07/08 15:08
-	112	430/\$.ccls. and ((organic adj acid adj ester))	USPAT	2003/07/08 15:11
-	5270	430/\$.ccls. and (organic adj acid)	USPAT	2003/07/08 15:12
-	280	430/270.1.ccls. and (organic adj acid)	USPAT	2003/07/08 15:12
-	269	(430/270.1.ccls. and (organic adj acid)) and (resist photoresist resin)	USPAT	2003/07/08 15:23
-	89	((430/270.1.ccls. and (organic adj acid)) and (resist photoresist resin)) and (visible near light)	USPAT	2003/07/08 15:30
-	44	((430/270.1.ccls. and (organic adj acid)) and (resist photoresist resin)) and (visible near light)) and negative	USPAT	2003/07/08 16:20
-	97	positive and ((photoacid acid) near generator) and (photosensitizer sensitizier) and (visible near light)	USPAT	2003/07/08 16:21
-	155	IMAI-G IMAI-GENICHI IMAI-GENJI	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 16:22
-	2	(positive and ((photoacid acid) near generator) and (photosensitizer sensitizier) and (visible near light)) and (IMAI-G IMAI-GENICHI IMAI-GENJI)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 16:33
-	2	("5801212").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 16:33